






10/724/41

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				ATTY DOCKET NO. INF-119		SERIAL NO. New Application		
				GRIT SCHWALBE ET AL.				
				FILING DECEMBER 1, 2003		GROUP Unknown 2813		
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
		5,660,681	08/26/97	FUKUDA ET AL.	438	695	08/19/96	
		6,232,237	05/15/01	TAMAOKA ET AL.	438	725	12/08/98	
		6,235,453	05/22/01	YOU ET AL.	430	329	07/07/99	
		2002/0076935	06/20/02	MAEX ET AL.	438	706	09/28/01	
		2001/0005635	06/28/01	KITAGAWA	438	710	12/14/00	
		2002/0146647	10/10/02	AOKI ET AL.	430	313	03/11/02	
		2002/0164877	11/07/02	CATABAY ET AL.	438	694	05/02/01	
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
		Article entitled "Limitation of HF-Based Chemistry for Deep-Submicron Contact Hole Cleaning on Silicides" by M.R. Baklanov et al., J. Electrochem. Soc., Vol. 145, No. 9 September 1998 by The Electrochemical Society, Inc., pp 3240-3246.						
		Article entitled "low-k dielectric etching" by D.J. Thomas et al., published March 2001 in Solid State Technology, pages 107, 108, 112-116 (www.solid-state.com)						
		Copy of German Office Action dated October 20, 2003						
EXAMINER 				DATE CONSIDERED 9/24/03				
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>								